Wurtzite phase control of self-assisted GaAs nanowires grown by molecular beam epitaxy

<u>T. Dursap</u>^{a*}, I. Dudko^{a,b}, M. Vettori^a, C. Botella^a, P. Regreny^a, N. Blanchard^c, M. Gendry^a, N. Chauvin^d, S. Walia^b, M. Bugnet^e, A. Danescu^a, J. Penuelas^{a*}

- a. Univ Lyon, CNRS, INSA Lyon, ECL, UCBL, CPE Lyon, INL, UMR 5270, 69130 Ecully, France
- b. Functional Materials and Microsystems Research Group and the Micro Nano Research Facility, RMIT University, Melbourne 3000, Australia
- c. Univ Lyon, CNRS, UCBL, ILM, 69622 Villeurbanne, France
- d. Univ Lyon, INSA Lyon, ECL, CNRS, UCBL, CPE Lyon, INL, UMR 5270, 69621 Villeurbanne, France
- e. Univ Lyon, CNRS, INSA Lyon, UCBL, MATEIS, UMR 5510, 69621 Villeurbanne, France
 - * email: thomas.dursap@ec-lyon.fr; jose.penuelas@ec-lyon.fr;

III-V semiconductor nanowires (NWs) obtained by the vapor-liquid-solid (VLS) mechanism exhibit a zinc-blende (ZB) or a wurtzite (WZ) structure [1] depending on the growth conditions, and more particularly on the amount of III and V element fluxes [2]. Controlling precisely the growth of the crystal phases of self-assisted GaAs NWs by molecular beam epitaxy (MBE) would be an important achievement for device applications [3]. Nevertheless, the optimized growth of WZ segments in nanowire geometry is still in its infancy, and major achievements have been reported only very recently [4-6].

In this work, we used an analytical growth model to show the existence of a stationary regime allowing the formation of a pure WZ phase, by a precise tuning of the V/III ratio. A slight change of the As flux indeed induces a modification of the catalyst droplet wetting angle in a desired range of values. The combination of an *in situ* reflection high energy electron diffraction (RHEED) evolution with high-resolution scanning transmission electron microscopy (STEM) and dark field TEM, as well as photoluminescence analysis confirmed the successful control of a micron-long pure WZ segment, obtained by MBE growth of self-assisted GaAs NWs [7].

- [1] F. Glas, et al, Physical Review Letters, 99 (2007), 146101.
- [2] F. Panciera, et al, Nano Letters, 20 (2020), 1669-1675.
- [3] E. M. T. Fadaly, et al, Nature, 580 (2020), 205-209.
- [4] T. Dursap, et al, Nanoscale Adv., 2 (2020), 2127-2134.
- [5] M. M. Jansen, et al, ACS Appl. Nano Mater., 3, 11 (2020), 11037-11047.
- [6] T. Dursap, et al, Nanotechnology, 32 (2021), 155602.

[7] This work was done as part of the ANR BEEP project (ANR-18-CE05-0017) and received funding from the European Union's Horizon 2020 research and innovation programme under the Marie Skłodowska-Curie grant agreement No 801512

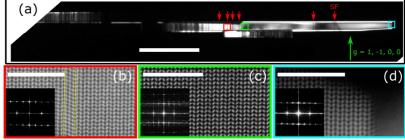


Figure 1: (a) Dark-field TEM image of the extended WZ segment. The red arrows indicate the stacking faults visible in the WZ segment. Scale bar is 500 nm. High-resolution STEM-HAADF images showing (b) the beginning or the extended WZ segment with a 3 MLs long ZB segment, (c) a portion of the extended WE segment and (d) the end of the extended WZ segment with the Ga droplet/NW interface. Scale bars on (b)-(d) are 5 nm.